

13        floating gate [therefrom] by [a] said second insulation layer, at least a portion of said control gate  
14        being disposed over a portion of said substrate and being separated therefrom by said second  
15        insulating layer;

16                an erase gate [generally placed on a second side] formed over a second one of said side  
17        walls and over at least a portion of said top surface of said floating gate and being separated  
18        [therefrom] from said second one of said side walls by said second insulation layer;

19                a drain region formed in a portion of said substrate proximate said control gate [generally  
20        disposed on a first side of said floating gate]; and

21                a source region [generally disposed on a second side of said floating gate] formed in a  
22        portion of said substrate proximate said erase gate.

*Part C2*

1        8. (Once Amended) A memory array disposed on a substrate comprising a plurality of memory  
2        cells each having a floating gate separated from said substrate by a first insulating layer, an erase  
3        gate, a control gate separated from said floating gate by a second insulating layer, a source  
4        region, and a drain region, comprising:

5                a plurality of rows and columns of interconnected memory cells wherein the control gates  
6        of memory cells in the same row are connected by a common word-line, the erase gates of the  
7        memory cells in the same rows are connected by a common erase line, [and] the source regions  
8        of the memory cells in the same rows are connected by a common source line, and the drain  
9        regions of memory cells in the same columns are commonly connected via a common drain line,  
10        wherein at least a portion of each said control gate is disposed over a portion of said substrate  
11        and separated therefrom by said second insulating layer; and

12                control circuit connecting to said word-lines, erase lines, source lines and drain lines for  
13        operating one or more memory cells of said memory array.

*Part C3*

1        16. (New) A semiconductor device having at least one transistor, the device comprising:  
2                a substrate having a channel region;  
3                a first insulating layer disposed over said channel region and over at least a portion of  
4        said substrate;

5                a floating gate generally disposed over said channel region and separated therefrom by  
6        said first insulating layer, said floating gate having at least two side walls and a top surface;